

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1896	SERIAL NO. 09/633,556
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Gurtej S. Sandhu et al.	
				FILING DATE August 7, 2000	GROUP 2813

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 01/15/02

U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
<div style="font-size: 2em; transform: rotate(-90deg); position: absolute; left: -40px; top: 0;">             [Handwritten initials/signatures]           </div>	AA	5,032,545	07/91	Doan et al.			
	AB	5,436,481	07/95	Egawa et al.			
	AC	5,378,645	01/95	Inoue et al.			
	AD	5,258,333	11/93	Shappir et al.			
	AE	5,518,946	05/96	Kuroda			
	AF	5,445,999	08/95	Thakur et al.			
	AG	5,382,533	01/95	Ahmad et al.			
	AH	5,663,077	09/97	Adachi et al.			
	AI	5,026,574	06/91	Economu et al.			
	AJ	5,026,574	06/91	Economu et al.			
	AK	5,612,558	3/1997 11/95	Harshfield			
	AL	5,719,083	2/1998 06/95	Komatsu			
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	AM	WO 96/39715	12/96	PCT			
	AN						
	AO						
	AP						
	AQ						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
<div style="font-size: 2em; transform: rotate(-90deg); position: absolute; left: -40px; top: 0;">             [Handwritten initials/signatures]           </div>	AR		Wolf, S., "Silicon Processing for the VLSI Era", Lattice Press 1990, Vol. 2, pp. 212-213.				
	AS		Wolf, S., "Silicon Processing for the VLSI Era", Lattice Press 1990, Vol. 2, pp. 188-189, 194-195, 609-614.				
	AT		Ko, L. et al., "The Effect of Nitrogen Incorporation into the Gate Oxide By Using Shallow Implantation of Nitrogen and Drive-In Process", IEEE 1996, pp. 32-35.				
EXAMINER <i>[Signature]</i>				DATE CONSIDERED 9/30/02			
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>							

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U.S. PATENT DOCUMENTS								
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<i>JS</i>	AA	5,760,475	06/98	Cronin				
<i>JS</i>	AB	5,834,372	11/98	Lee				
<i>JS</i>	AC	5,619,057	04/98	Komatsu				
<i>JS</i>	AD	5,633,036	05/97	Seebauer et al.				
<i>JS</i>	AE	6,054,396	04/00	Doan				
<i>JS</i>	AF	6,174,821	01/01	Doan				
<i>JS</i>	AG	5,939,750	08/99	Early				
<i>JS</i>	AH	5,254,489	10/93	Nakata				
<i>JS</i>	AI	5,464,792	11/95	Tseng et al.				
<i>JS</i>	AJ	5,620,908	04/97	Inoh et al.				
<i>JS</i>	AK	5,716,864	02/98	Abe				
<i>JS</i>	AL	5,972,783	10/99	Arai et al.				
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		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
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	AQ							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AR		Doyle, B. et al., "Simultaneous Growth of Different Thickness Gate Oxides in Silicon CMOS Processing", IEEE Vol. 16 (7), July 1995, pp. 301-302.					
	AS		Kuroi, T. et al., "The Effects of Nitrogen Implantation Into P+Poly-Silicon Gate on Gate Oxide Properties", 1994 Sympos. on VLSI Technology Digest of Technical Papers, IEEE 1994, pp. 107-108.					
	AT		Liu, C.T. et al., "Multiple Gate Oxide Thickness for 2GHz System-on-a-Chip Technologies", IEEE 1998, pp. 589-592.					
EXAMINER <i>Noreen Selwitz</i>				DATE CONSIDERED <i>9/30/02</i>				
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<i>JS</i>	AA	6,091,109	07/00	Hasegawa				
<i>JS</i>	AB	6,080,682	06/00	Ibok				
<i>JS</i>	AC	5,685,949	11/97	Yashima				
<i>JS</i>	AD	6,268,296 B1	07/01	Misium et al.				
<i>JS</i>	AE	6,232,244 B1	05/01	Ibok				
	AF							
	AG							
	AH							
	AI							
	AJ							
	AK							
	AL							
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	AT							
EXAMINER <i>Wesley Schultz</i>				DATE CONSIDERED <i>9/30/02</i>				
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